

Amended Patent Claims (Art. 19 PCT)

1. A method for producing a blank for a component of laser active quartz glass, comprising the following steps:
 - 5 a) providing a dispersion with a solids content of at least 40% by wt. which contains SiO₂ nanopowder and dopants, including a cation of the rare earth metals or of the transition metals in a liquid,
 - b) granulation by moving the dispersion with withdrawal of moisture until the formation of a doped SiO₂ granulate of spherical porous
10 granulate grains having a moisture content of less than 35% by wt. and a density of at least 0.95 g/cm³,
 - c) drying and purifying the SiO₂ granulate by heating to a temperature of at least 1000°C with formation of doped porous SiO₂ granules having an OH content of less than 10 ppm, and
15 d) sintering or melting the doped SiO₂ granules in a reducing atmosphere with formation of the blank of doped quartz glass, including a gas pressure sintering, which comprises the following steps:
 - 20 aa) heating the SiO₂ granules to a melting temperature of at least 1600°C while applying and maintaining a negative pressure;
 - bb) holding at the melting temperature at an overpressure ranging from 5 bar to 15 bar for a melting period of at least 30 min with formation of the quartz glass blank;
 - 25 cc) cooling the quartz glass blank while maintaining an overpressure.
2. The method according to claim 1, characterized in that an initial solids content of at least 50% by wt. is set in the dispersion.
3. The method according to any one of the preceding claims, characterized in that the SiO₂ granulate obtained according to step b) has a BET surface
30 area ranging from 40 m²/g to 70 m²/g.

4. The method according to claim 3, characterized in that the SiO₂ granulate obtained according to step b) has a BET surface area of at least 50 m²/g.
5. The method according to any one of the preceding claims, characterized in that the spherical porous granulate grains have a grain size of less than 500 µm.
6. The method according to any one of the preceding claims, characterized in that the SiO₂ granulate is dried and purified under a chlorine-containing atmosphere.
7. The method according to any one of the preceding claims, characterized in that the SiO₂ granulate is dried and purified at a temperature of at least 1050°C.
8. The method according to any one of the preceding claims, characterized in that drying and purifying of the porous granulate is performed under an oxygen-containing atmosphere.
9. The method according to any one of the preceding claims, characterized in that the porous SiO₂ granules obtained according to step c) have an OH content of less than one wt ppm.
10. The method according to any one of the preceding claims, characterized in that the porous SiO₂ granules obtained according to step c) have a BET surface area of less than 20 m²/g.
11. The method according to any one of the preceding claims, characterized in that the SiO₂ granules are thermally densified prior to step d).
12. The method according to any one of the preceding claims, characterized in that the quartz glass blank is annealed at a temperature of at least 1120°C for a retention period of at least 40 h.
13. The method according to any one of the preceding claims, characterized in that the SiO₂ granules according to step d) are molten in a mold.

14. The method according to any one of the preceding claims, characterized in that the SiO_2 blank according to step d) is three-dimensionally homogenized.
- 5 15. The method according to any one of the preceding claims, characterized in that a bulk body with a radially inhomogeneous refractive index distribution is formed from SiO_2 granules of different refractive index, and that the bulk body is sintered or molten to obtain the SiO_2 blank.
- 10 16. Use of an SiO_2 blank obtained according to a method as claimed in claims 1 to 15, as a core material for a fiber laser, as an optical filter or as a cladding tube for laser.